L	Hits	Search Text	DB	Time stamp
Number				
1	0	438/240, 250, 253, 393, 399.pn. and (Ta or	USPAT;	2003/10/27
		tantalum) and CVD and (capacitor) and	US-PGPUB;	15:37
	ļ	(precursor) and (source adj gas) and (oxygen) and (dielectric) and (tantalum	EPO; JPO; DERWENT	
		(oxygen) and (dielectric) and (tantalum adj pentamethoxide or tantalum adj	DERWENT	
		pentaethoxide)		
2	0	-	USPAT;	2003/10/27
2		tantalum) and CVD and (capacitor) and	US-PGPUB;	15:38
		(precursor) and (source adj gas) and	EPO; JPO;	10.00
		(oxygen) and (dielectric) and (tantalum	DERWENT	
		adj pentamethoxide or tantalum adj		
		pentaethoxide)		
-	15673	(Ta or tantalum) and CVD	USPAT;	2003/05/27
			US-PGPUB;	09:04
			EPO; JPO;	
	007	(m tastalam) and GID and (managitam)	DERWENT	2002/05/26
ļ -	897	`	USPAT; US-PGPUB;	2003/05/26 15:23
		and (precursor)	EPO; JPO;	13.23
			DERWENT	
_	102	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/26
		and (precursor) and (source adj gas) and	US-PGPUB;	15:27
]	(oxygen)	EPO; JPO;	
1			DERWENT	
-	96	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/30
		and (precursor) and (source adj gas) and	US-PGPUB;	16:08
		(oxygen) and (dielectric)	EPO; JPO;	
			DERWENT	0000/05/06
-	30822	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/26
		and (precursor) and (source adj gas) and	US-PGPUB;	15:28
		(oxygen) and (dielectric) (lower adj	EPO; JPO; DERWENT	1
l _	21	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/26
	21	and (precursor) and (source adj gas) and	US-PGPUB;	15:28
		(oxygen) and (dielectric) and (lower adj	EPO; JPO;	
		electrode)	DERWENT	
-	12	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/27
		and (precursor) and (source adj gas) and	US-PGPUB;	16:44
		(oxygen) and (dielectric) and (lower adj	EPO; JPO;	
		electrode) and (upper adj electrode)	DERWENT	2002/05/26
-	12	'	USPAT; US-PGPUB;	2003/05/26
		and (precursor) and (source adj gas) and (oxygen) and (dielectric) and (lower adj	EPO; JPO;	15:32
		electrode) and (upper adj electrode) and	DERWENT	
		(substrate)		
_	0	6207489.pn. and purging	USPAT;	2003/05/27
			US-PGPUB;	09:06
			EPO; JPO;	
			DERWENT	
-	2	6207489.pn.	USPAT;	2003/05/28
			US-PGPUB;	13:38
	1		EPO; JPO;	
l _	2	20020100959.pn.	DERWENT USPAT;	2003/05/27
-	2	20020100939.pii.	US-PGPUB;	09:25
			EPO; JPO;	
			DERWENT	
-	0	20020100959.pn. and (purge or purging)	USPAT;	2003/05/27
			US-PGPUB;	09:26
			EPO; JPO;	
			DERWENT	
_	0	20020100959.pn. and (purge or purging or	USPAT;	2003/05/27
		exhaust)	US-PGPUB;	09:27
			EPO; JPO;	
_	0	6207489.pn. and (purge or purging or	DERWENT USPAT;	2003/05/27
		exhaust)	US-PGPUB;	09:28
			EPO; JPO;	
			DERWENT	j
		• • • • • • • • • • • • • • • • • • • •		

_	0	6218260.pn. and (purge or purging or exhaust)	USPAT; US-PGPUB; EPO; JPO;	2003/05/27 09:29
			DERWENT	
	2	20020006708.pn. and (purge or purging or	USPAT;	2003/05/27
	-	exhaust)	US-PGPUB;	17:50
		Childusty	EPO; JPO;	
			DERWENT	
	9	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/05/27
_		and (precursor) and (source adj gas) and	US-PGPUB;	16:57
Ì		(oxygen) and (dielectric) and (lower adj	EPO; JPO;	10.07
		electrode) and (upper adj electrode) and	DERWENT	
		(Ru or Pt or Ir.)	DBINDINI	
	1		USPAT;	2003/05/27
_		65/6299.pm. and (Ru Of FC Of II.)	US-PGPUB;	17:00
			EPO; JPO;	1,,,,,,,
			DERWENT	
	2	6482740.pn. and (Ru or Pt or Ir.)	USPAT;	2003/05/27
-	2	0402/40.pm. and (Na Of 10 Of 11.)	US-PGPUB;	17:08
!			EPO; JPO;	17.00
			DERWENT	
_	1	6376299.pn. and (Ru or Pt or Ir.)	USPAT;	2003/05/27
	*	00,0255.pii. uiia (Na 01 10 01 11.)	US-PGPUB;	17:17
			EPO; JPO;	-··
			DERWENT	
_	0	6376299.pn. and (Ru or Pt or Ir.) and	USPAT;	2003/05/27
	ا	(purge or purging or exhaust)	US-PGPUB;	17:16
1		(purge or purgring or emiddes)	EPO; JPO;	-/
			DERWENT	
_	1	20020006708.pn. and (Ru or Pt or Ir.)	USPAT;	2003/05/28
	_	2002000,00.Pitt and (via of to the first)	US-PGPUB;	12:01
			EPO; JPO;	
			DERWENT	
_	1	20020100959.pn. and (Ru or Pt or Ir.)	USPAT;	2003/05/27
		-	US-PGPUB;	17:28
	1		EPO; JPO;	
			DERWENT	
-	0	20020100959.pn. and (Ru or Pt or Ir.) and	USPAT;	2003/05/27
		(purge or purging)	US-PGPUB;	17:29
			EPO; JPO;	
			DERWENT	
-	1	20020100959.pn. and (Ru or Pt or Ir.) and	USPAT;	2003/05/27
		(flow adj rate)	US-PGPUB;	17:30
			EPO; JPO;	
		,	DERWENT	2002/05/27
[-	0	6372598.pn. and (Ru or Pt or Ir.) and	USPAT;	2003/05/27
		(flow adj rate)	US-PGPUB;	17:30
			EPO; JPO;	
1	_	(272500 /2 25	DERWENT	2002/05/27
-	1	6372598.pn. and (Ru or Pt or Ir.)	USPAT;	2003/05/27
			US-PGPUB; EPO; JPO;	17:31
			DERWENT	
	,	20020006709 nn and /titanium add mitrida	USPAT;	2003/05/27
-	1	20020006708.pn. and (titanium adj nitride or tantalum adj nitride or tungsten adj	US-PGPUB;	17:57
		nitride)	EPO; JPO;	- ' - ' '
		IIICIIUC/	DERWENT	
I _	1	20020006708.pn. and (titanium adj nitride	USPAT;	2003/05/27
		or tantalum adj nitride or tungsten adj	US-PGPUB;	17:58
		nitride) and (precursor)	EPO; JPO;	
			DERWENT	
-	1	20020006708.pn. and (Ru or Pt or Ir.) and	USPAT;	2003/05/28
	1	(bottom or lower adj electrode)	US-PGPUB;	12:13
		,	EPO; JPO;	
1			DERWENT	
-	1	20020006708.pn. and (argon or nitrogen)	USPAT;	2003/09/17
			US-PGPUB;	15:54
			EPO; JPO;	
			DERWENT	

-	0	20020006708.pn. and (sccm)	USPAT;	2003/05/28
			US-PGPUB;	12:16
			EPO; JPO;	
			DERWENT	/
-	1	20020006708.pn. and (flow)	USPAT;	2003/05/28
			US-PGPUB;	13:27
			EPO; JPO;	
1	_		DERWENT	/
-	0	20020006708.pn. and (flow adj rate)	USPAT;	2003/05/28
			US-PGPUB;	13:27
			EPO; JPO;	
		20020006700 ()	DERWENT	2003/05/28
-	U	20020006708.pn. and (sccm)	USPAT; US-PGPUB;	13:28
			EPO; JPO;	13.20
			DERWENT	
l	1	20020006708.pn. and (flow)	USPAT;	2003/05/28
-	_	20020000700.pm. and (110w)	US-PGPUB;	13:32
			EPO; JPO;	••••
			DERWENT	! !
_	0 !	20020006708.pn. and (cubic adj	USPAT;	2003/05/28
	_	centimeters)	US-PGPUB;	13:33
			EPO; JPO;	
	•		DERWENT	
-	2	6207489.pn.	USPAT;	2003/05/28
]	_	•	US-PGPUB;	13:38
			EPO; JPO;	
			DERWENT	
-	1	6207489.pn. and flow	USPAT;	2003/05/28
			US-PGPUB;	13:41
			EPO; JPO;	
		`	DERWENT	
-	0	6207489.pn. and sccm	USPAT;	2003/05/28
			US-PGPUB;	13:42
			EPO; JPO;	
			DERWENT	/
-	1	6207489.pn. and flow adj rate	USPAT;	2003/05/28
			US-PGPUB;	13:42
			EPO; JPO;	
		100 (0.40 OFO OFO 000 200 (F	DERWENT	2002/00/22
-	96		USPAT;	2003/09/23
		and CVD and (capacitor) and (precursor)	US-PGPUB; EPO; JPO;	15:45
		and (source adj gas) and (oxygen) and	DERWENT	
	1	(dielectric) 20020006708.pn. and (chemical adj vapor	USPAT;	2003/09/17
-			US-PGPUB;	16:58
		adj deposition)	EPO; JPO;	
			DERWENT	
_	156	atomic adj layer adj deposition and	USPAT;	2003/09/17
		(atomic adj layer adj epitax\$3)	US-PGPUB;	17:24
		,	EPO; JPO;	
			DERWENT	
-	0		USPAT;	2003/09/17
1		(atomic adj layer adj epitax\$3)) near	US-PGPUB;	17:28
		dielectric adj insulat\$3	EPO; JPO;	
			DERWENT	
-	0	(atomic adj layer adj deposition and	USPAT;	2003/09/17
1		(atomic adj layer adj epitax\$3)) with	US-PGPUB;	17:28
		dielectric adj insulat\$3	EPO; JPO;	
] _	1	DERWENT	2002/00/17
_	0		USPAT;	2003/09/17
		(atomic adj layer adj epitax\$3)) near12	US-PGPUB;	17:29
		dielectric adj insulat\$3	EPO; JPO;	
1_	_	latomic add layer add denocition and	DERWENT USPAT;	2003/09/17
1	0	atomic adj layer adj deposition and atomic adj layer adj epitax\$3 and	US-PGPUB;	17:30
	[dielectric adj insulat\$3 and	EPO; JPO;	1
		international adj business adj machines	DERWENT	
_	6		USPAT;	2003/09/17
	1	atomic adj layer adj epitax\$3 and	US-PGPUB;	19:06
		dielectric adj insulat\$3	EPO; JPO;	
	1		DERWENT	
				•

-	1	6203613.pn. and CVD	USPAT;	2003/09/17
			US-PGPUB;	19:09
			EPO; JPO;	
			DERWENT	
-	0	6203613.pn. and compacitor	USPAT;	2003/09/17
			US-PGPUB;	19:10
			EPO; JPO;	
		6000610	DERWENT	2002/00/17
-	2	6203613.pn. and capacitor	USPAT;	2003/09/17
			US-PGPUB;	19:10
			EPO; JPO; DERWENT	
	1	20020006709 pp and Bu	USPAT;	2003/09/22
-	† †	20020006708.pn. and Ru	US-PGPUB;	16:28
			EPO; JPO;	10.20
			DERWENT	
_	ا م	6207489.pn. and (tantalum adj	USPAT;	2003/09/23
		pentamethoxide)	US-PGPUB;	10:48
]		pericame directacy	EPO; JPO;	
			DERWENT	
_	2	(tantalum adj pentamethoxide) and	USPAT;	2003/09/23
	_	capacitor	US-PGPUB;	12:14
		-	EPO; JPO;	
			DERWENT	
-	0	() <u>F</u> ,	USPAT;	2003/09/23
		capacitor and precursor	US-PGPUB;	12:18
			EPO; JPO;	
			DERWENT	
-	38	(tantalum adj ethylate) and capacitor and	USPAT;	2003/09/23
		electrode	US-PGPUB;	12:20
			EPO; JPO;	
			DERWENT	0000/00/00
-	23		USPAT;	2003/09/23
İ		electrode and precursor	US-PGPUB;	12:20
			EPO; JPO;	
	22	(toutalism and atherland) and manageton and	DERWENT USPAT;	2003/09/23
-	23	(tantalum adj ethylate) and capacitor and electrode and precursor	US-PGPUB;	12:21
		electione and precursor	EPO; JPO;	12.21
			DERWENT	
_	۸ ا	6110531.pn. and (tantalum adj	USPAT;	2003/09/23
1	Ĭ	pentamethoxide) and capacitor and	US-PGPUB;	12:42
		electrode	EPO; JPO;	
			DERWENT	
-	0	6110531.pn. and (tantalum adj	USPAT;	2003/09/23
		pentamethoxide)	US-PGPUB;	12:42
			EPO; JPO;	
			DERWENT	
-	0		USPAT;	2003/09/23
		pentamethoxide)	US-PGPUB;	12:43
			EPO; JPO;	
	_	0F042F04	DERWENT	2002/00/22
-	0		USPAT;	2003/09/23
		pentamethoxide)	US-PGPUB; EPO; JPO;	12:45
	1		DERWENT	
_	0	 (tantalum adj pentamethoxide) and	USPAT;	2003/09/23
-		(tantalum ad) pentamethoxide) and capacitor and electrode	US-PGPUB;	14:19
		capacitoi and electione	EPO; JPO;	
			DERWENT	
_	l 0	438/240,250,253,393,399(Ta or tantalum)	USPAT;	2003/09/23
	I	and CVD and (capacitor) and (precursor)	US-PGPUB;	16:06
		and (source adj gas) and (oxygen) and	EPO; JPO;	
		(dielectric) and (tantulum adj	DERWENT	
		pentamethoxide or tantulum adj	1	
		pentaethoxide)		
-	0	438/240,250,253,393,399(Ta or tantalum)	USPAT;	2003/09/23
	1	and CVD and (capacitor) and (precursor)	US-PGPUB;	15:51
		and (source adj gas) and (oxygen) and	EPO; JPO;	
1		(dielectric) and ((tantulum adj	DERWENT	
		pentamethoxide) or (tantulum adj		
1	I	pentaethoxide))	L	<u> </u>

	·			0000/00/00
-	0	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/09/23
		<pre>and (precursor) and (source adj gas) and (oxygen) and (dielectric) and ((tantulum)</pre>	US-PGPUB; EPO; JPO;	15:52
		adj pentamethoxide) or (tantulum adj	DERWENT	
		pentaethoxide))	DERWENT	
_	1	(Ta or tantalum) and CVD and (capacitor)	USPAT;	2003/09/23
	-	and (precursor) and (source adj gas) and	US-PGPUB;	15:52
		(oxygen) and (dielectric) and ((tantalum	EPO; JPO;	
		adj pentamethoxide) or (tantalum adj	DERWENT	
		<pre>pentaethoxide))</pre>		
-	0	438/240,250,253,393,396,399(Ta or	USPAT;	2003/09/23
		tantalum) and CVD and (capacitor) and	US-PGPUB;	16:08
		(precursor) and (source adj gas) and	EPO; JPO; DERWENT	
		(oxygen) and (dielectric) and (tantulum adj pentamethoxide or tantulum adj	DEKMENI	
		pentaethoxide)		
_	l 0	5919963.pn. and precursor	USPAT;	2003/10/23
		p = 1 = 1	US-PGPUB;	15:52
!			EPO; JPO;	
			DERWENT	ł
. -	0	5919963.pn. and (precursor or absorption)	USPAT;	2003/10/23
			US-PGPUB;	16:23
			EPO; JPO; DERWENT	
	1	20020025628.pn. and purging	USPAT;	2003/10/24
-		20020023626.pii. and purgring	US-PGPUB;	11:45
			EPO; JPO;	=
	}		DERWENT	
-	0	20020025628.pn. and ((titanium adj	USPAT;	2003/10/24
		nitride) or (tantalum adj nitride) or	US-PGPUB;	14:22
		(tungsten adj nitride))	EPO; JPO;	
			DERWENT	2003/10/24
-	0	6203613.pn. and ((titanium adj nitride) or (tantalum adj nitride) or (tungsten	USPAT; US-PGPUB;	2003/10/24 14:50
		or (tantalum adj hitride) or (tungsten adj nitride))	EPO; JPO;	14.50
		auj mittide,,	DERWENT	
_	1	6203613.pn. and (flow rate or sccm)	USPAT;	2003/10/24
	_	, , , , , , , , , , , , , , , , , , , ,	US-PGPUB;	17:53
			EPO; JPO;	
	1		DERWENT	2002/10/24
-	1	20020025628.pn. and (flow rate or sccm)	USPAT; US-PGPUB;	2003/10/24
			EPO; JPO;	14.55
			DERWENT	
_	147709	6203613.pn. and nitrogen or argon	USPAT;	2003/10/24
			US-PGPUB;	17:54
			EPO; JPO;	
			DERWENT	0000/15/5/
-	1	6203613.pn. and (nitrogen or argon)	USPAT;	2003/10/24
			US-PGPUB;	17:56
			EPO; JPO; DERWENT	
_	1	6203613.pn. and (nitrogen or argon same	USPAT;	2003/10/24
	1	inert)	US-PGPUB;	17:56
			EPO; JPO;	
			DERWENT	
-	1	20020100959.pn. and precursor	USPAT;	2003/10/27
			US-PGPUB;	10:16
			EPO; JPO;	
1_	0	20020100959.pn. and absorption	DERWENT USPAT;	2003/10/27
-		20020100909.pit. and absorption	US-PGPUB;	10:18
			EPO; JPO;	-5.25
		·	DERWENT	
-	0	20020100959.pn. and (absorption or	USPAT;	2003/10/27
		absorb)	US-PGPUB;	10:19
			EPO; JPO;	
		6202612 mm and /hambalton and ablantation	DERWENT	2002/10/27
_	0	6203613.pn. and (tantalum adj chloride)	USPAT; US-PGPUB;	2003/10/27
	1		EPO; JPO;	14.43
	1		DERWENT	
	1	I	1	L